

**IN THE SPECIFICATION**

Please replace the paragraph that begins on page 2, line 11, with the following amended paragraph:

The present invention ~~[[to]]~~ provides a substrate with a single-crystal lattice which makes it possible to repair the local surface defects, to ensure planarity and surface homogeneity, and to ensure continuity of the single-crystal lattice of this surface.

Please replace the paragraph that begins on page 6, line 4, with the following amended paragraph:

Next, the nitride 3, ~~[[followed-by]]~~ followed by the oxide 2 and finally the single-crystal silicon of the substrate 1 are anisotropically etched in a conventional manner with the aid of a photolithography operation in order to form the trench 4.